

Figure 1.

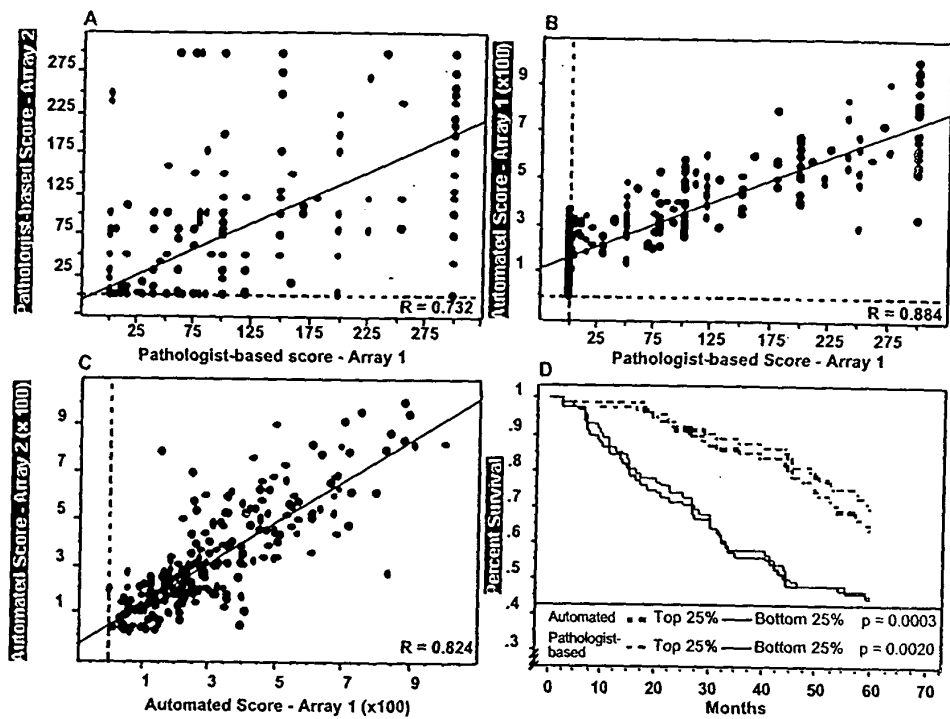


Figure 2

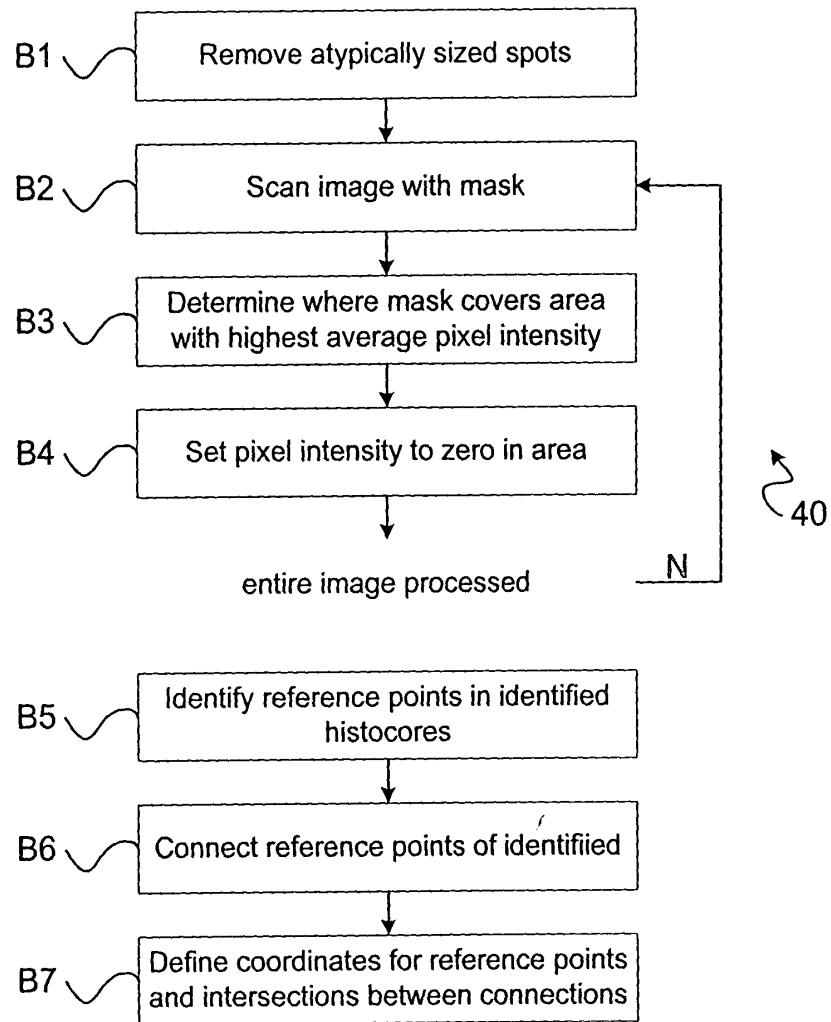


FIG. 3

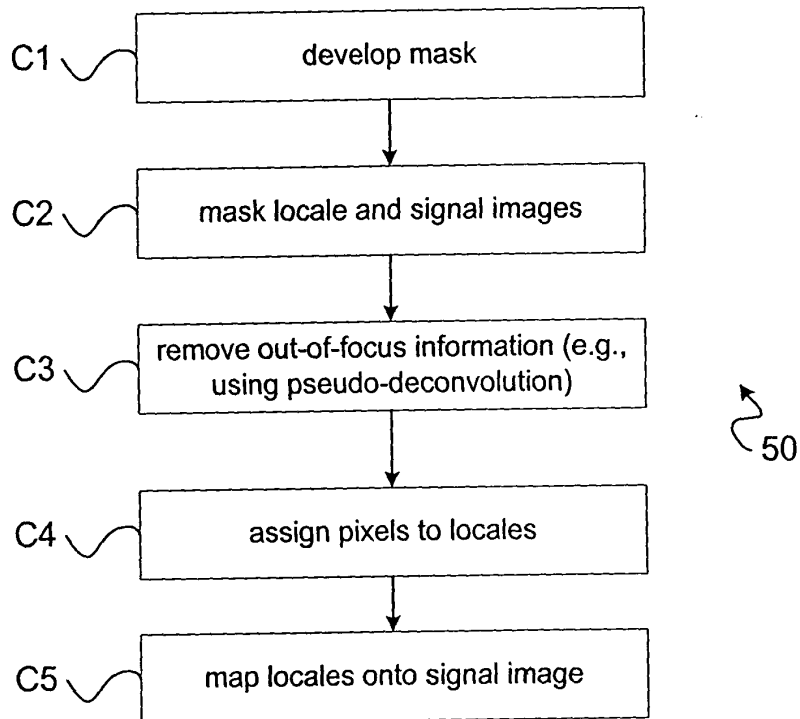


FIG. 4

100
↳

FIG. 5 is a schematic diagram of a device 100. The device 100 includes a substrate 110, a first layer 120, and a second layer 130. The first layer 120 is disposed on the substrate 110 and includes a grid of openings 120. The second layer 130 is disposed on the first layer 120 and includes a grid of openings 130. The openings 120 and 130 are arranged in a staggered pattern.

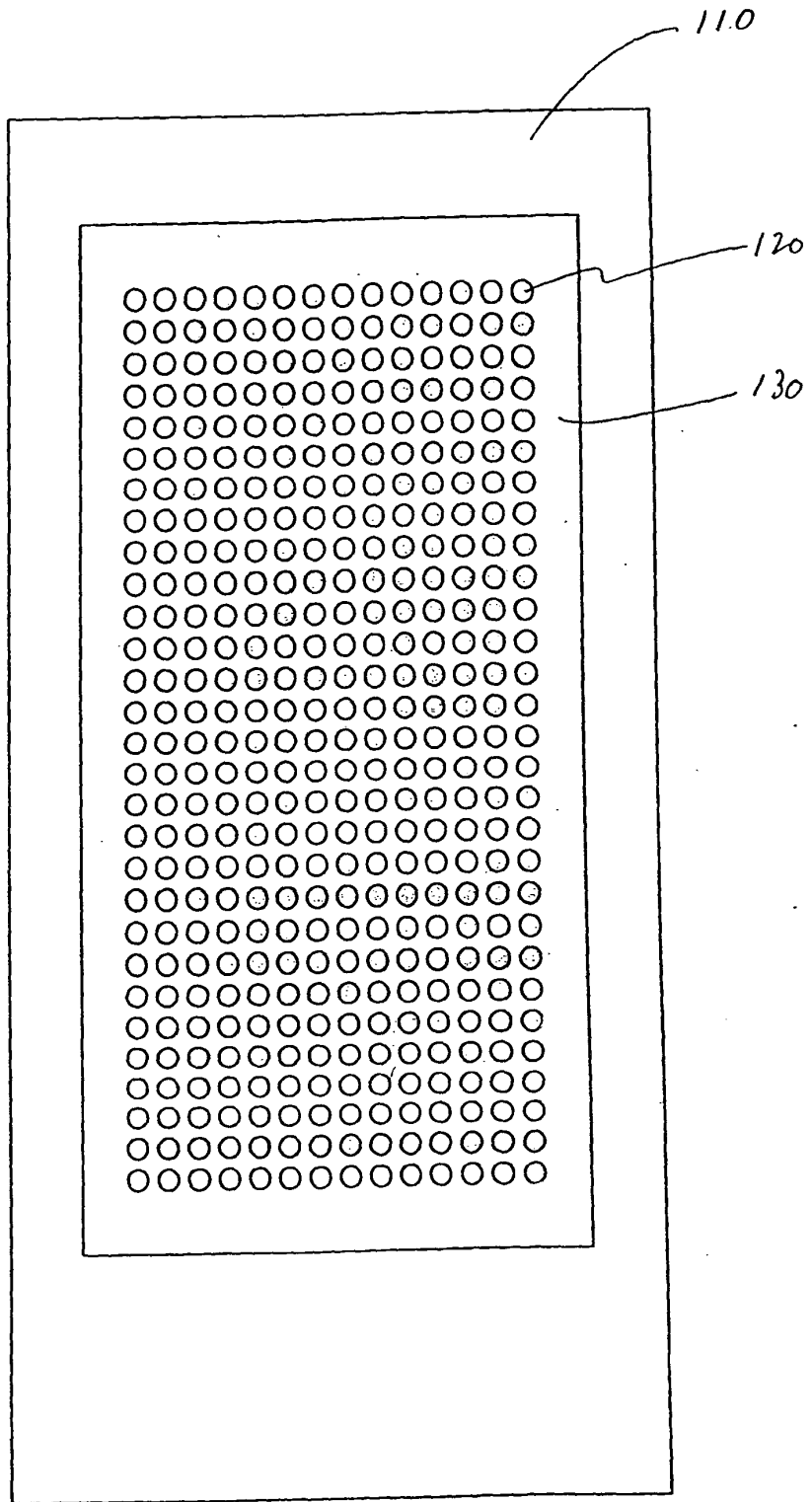


FIG. 5

FIG. 6 is a schematic diagram of a system 200 for processing a substrate 100. The system 200 includes a substrate 100, a processing chamber 210, a gas inlet 220, a gas outlet 230, a gas supply 240, a gas control system 250, and a gas monitor 260. The system 200 is connected to a gas supply 290 via a gas line 270. The system 200 is also connected to a gas control system 280 via a control line 285. The system 200 is further connected to a gas monitor 290 via a monitor line 295. The system 200 is shown in a perspective view.

200 →

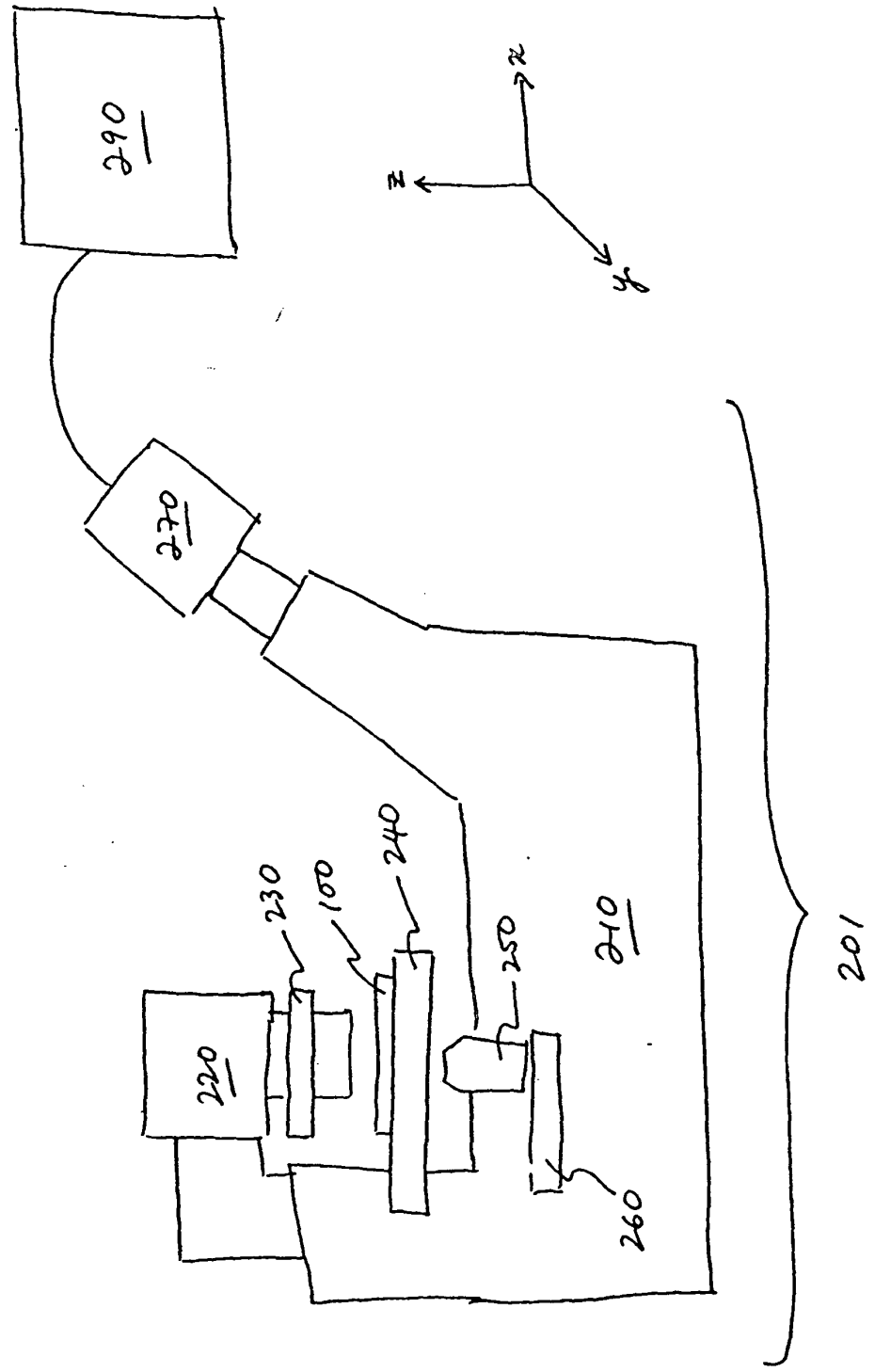


FIG. 6